Advanced techniques for fault injection attacks on integrated circuits

Paul GRANDAMME

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E LABORATOIRE HUBERT CURIEN

Une école de l'IMT

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Introd	uction

Flash memories

Laser Fault Injection on unpowered devices

X-Ray Fault Injection

Conclusion













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Advanced techniques for fault injection attacks on integrated circuits

Introduction	Flash memories	Laser Fault Injection on unpowered devices	Х-
Context			

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(-Ray Fault Injection

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Conclusion

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Conclusion





Conclusion



Definition

Disturbing the integrated circuit to **modify its behavior** in order to obtain information or disable internal protection mechanisms.



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Introduction	Flash memories	Laser Fault Injection on unpowered devices	X-Ray Fault Injection	Conclusion
Chronology				
2002	2009			
Photoflash	$UV\ lamp^2$			
photo ¹	Laser ³			

¹Sergei P. Skorobogatov and Ross J. Anderson. "Optical Fault Induction Attacks". In: CHES 2002.

² Jörn-Marc Schmidt, Michael Hutter, and Thomas Plos. "Optical Fault Attacks on AES: A Threat in Violet". In: FDTC 2009.

³Sergei P. Skorobogatov. "Local Heating Attacks on Flash Memory Devices". In: IEEE HOST. 2009.

⁴Brice Colombier et al. "Laser-induced Single-bit Faults in Flash Memory: Instructions Corruption on a 32-bit Microcontroller". In: IEEE HOST 2019.

⁵Alexandre Menu et al. "Single-bit Laser Fault Model in NOR Flash Memories: Analysis and Exploitation". In: FDTC 2020.

⁶Brice Colombier et al. "Multi-Spot Laser Fault Injection Setup: New Possibilities for Fault Injection Attacks". In: CARDIS. 2022.

Introduction	Flash memories	Laser Fault Injection on unpowered devices	X-Ray Fault Injection	Conclusion
Chronology				
2002	2009	2019 2020		
Photoflash photo ¹	UV lamp ² Laser ³	Full comprehension of the fault model ^{4,5}		

¹Sergei P. Skorobogatov and Ross J. Anderson. "Optical Fault Induction Attacks". In: CHES 2002.

² Jörn-Marc Schmidt, Michael Hutter, and Thomas Plos. "Optical Fault Attacks on AES: A Threat in Violet". In: FDTC 2009.

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Introduction	Flash memories	Laser Fault Injection on unpowered devices	X-Ray Fault Injection	Conclusion
Photoelectr	ic effect			
	$E_{photon} = \frac{hc}{\lambda}$			

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Photoelect	ric effect			



Introduction	Flash memo	ries Laser F	ault Injection on 1	inpowered devices	X-Ray Fault Injection	Conclusion
Photo	electric effec	t				
1	E _{phot}	$c_{DD} = \frac{hc}{\lambda}$		E _{photon} >	$E_{gap} \Rightarrow \lambda < rac{hc}{E_{gap}} pprox 1100$) nm
	Conduction band	● Electro	n			
Energy (eV	$igstar{} E_{gap}$	$E_{photon} =$	$rac{hc}{\lambda} > E_{gap}$			
_	Valence band	O Hole				





Advanced techniques for fault injection attacks on integrated circuits

Context

State of the art

Almost all attacks are carried out on powered devices



Context

State of the art

Almost all attacks are carried out on powered devices



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State of the art

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Introduction	Flash memories	Laser Fault Injection on unpowered devices	X-Ray Fault Injection	Conclusio
Context				
State of	the art			
Almost all	attacks are carr	ied out on powered devices		



Introduction	Flash memories	Laser Fault Injection on unpowered devices	X-Ray Fault Injection	Conclusion
Context				

Problem

Can laser faults be injected into unpowered devices?

POP project

Attack unpowered devices

- No detection is possible \Rightarrow No reaction possible
- No synchronisation required



Idea

• Corrupt stored data : non-volatile memories (Flash)

1 Flash memory operation

- 2 Laser Fault Injection on unpowered devices
- **3** X-Ray Fault Injection
- 4 Conclusion

Conclusion

Floating gate transistors



Conclusion

Floating gate transistors







Read mechanism



Read mechanism in NOR Flash memories

1 Flash memory operation

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Abstraction levels



Abstraction levels



- Energy of the laser beam
- \Rightarrow Temperature rise
- \Rightarrow Floating gate transistors discharge^a

Laser beam intensity :

$$I(r) = I_0 \cdot e^{-\frac{2r^2}{\omega_0^2}}$$
 avec $\omega_0 = \frac{2\lambda}{\pi \times NA}$

FWHM criterion \Rightarrow

$$d_0 = \omega_0 \sqrt{\frac{\ln 2}{2}} \approx 5 \,\mu \mathrm{m}$$

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^aSergei P. Skorobogatov. "Local Heating Attacks on Flash Memory Devices". In: *IEEE HOST*. 2009.



Heatmap induced by laser exposure (numerical simulation with $\lambda = 1064$ nm et NA = 0.16)

Abstraction levels



Introduction	Flash memories	Laser Fault Injection on unpowered devices	X-Ray Fault Injection	Conclusion
Logical leve				

From the physical level :





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Logical leve				

From the physical level :





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Abstraction levels



Memory level

Flash memory

• Used in particular to store code, constants, etc.

Memory level

Flash memory

• Used in particular to store code, constants, etc.

Source code

Stored in Flash

• Fault injection ⇒ Code corruption

Abstraction levels



Laser injection bench





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Characteristics

- Laser source 1064 nm (near-IR)
- Laser pulse of 0.9 s
- Spot of 5 µm with x20 magnification
- Backside view possible thanks to infrared camera
- Laser bench commonly used for laser injection on powered circuits

Experimental material

Target

- 32-bit microcontroller (CMOS 80 nm) dedicated to IoT applications
- ARM Cortex-M3 core
- 128 kB of Flash memory (128 pages of 1 kB)
- Open on the backside for access to the substrate



Injected faults mapping

Red	quire: $X_{min}, X_{max}, X_{step}, Y_{min}, Y_{max}, Y_{step}$
1:	for $x \in \operatorname{range}(X_{\min}, X_{\max}, X_{step})$ do
2:	for $y \in \text{range}(Y_{min}, Y_{max}, Y_{step})$ do
3:	Memory initialization
4:	do
5:	Move the laser to (x,y)
6:	Switch off the target
7:	for <i>i</i> ∈ [0, , 999] do
8:	Laser shot
9:	Switch on the target
10:	Flash memory read
11:	while $\#$ faults == 0
12:	mapping[x][y] = #faults
13:	return mapping[x][y]





• Memory initialized to 0x00000000 (programmed) before laser exposure



Mapping of injected faults. $P_{laser} = 1 \text{ W}, f_{laser} = 1 \text{ Hz}, T_{pulse} = 0.9 \text{ s}$

 \Rightarrow Values and addresses of known faults (bitsets only)

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Experimental distribution





- 2.2 faulty bits on average on a memory initialized at 0x00000000
- Monobit faults in 33% of cases
- No correlation between #shots and #faults

Reverse engineering 1/2



Reverse engineering at the page level

Reverse engineering 2/2



Reverse engineering at the bit level

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Abstraction levels



Introduction

Persistant Fault Analysis (PFA) : Theory⁷ (CHES 2018)

- Permanent fault injection in the substitution box (S-Box)
 - AES : 256 known values stored in Flash memory
- Statistical study of the bytes in ciphertext
- Exploiting the bias to find the encryption key



⁷Fan Zhang et al. "Persistent Fault Analysis on Block Ciphers". In: IACR TCHES. (2018).

Appearance of byte values



Experimental results (IACR TCHES 2024)

- Reverse engineering of the *firmware* ⇒ S-box stored between addresses 0x080012F4 and 0x080013F3
- Prom the previous mapping
 - \Rightarrow the position (x,y) = (44.3,300) is in the S-box range
- Solution (a) Constraint (c) Constrain

Successful PFA

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First experimental use of PFA on an unpowered device





Abstraction levels



Synthesis

- · Fault injection in unpowered components
- · Possibility of injecting localized faults into Flash memories
- Single-bit, permanent, bitset faults
- Description of a complete fault model
- Application: Persistent Fault Analysis (PFA)

Consequences

- Securing circuits dedicated to IoT applications (EDAC codes)
- Increased interest in the PFA
 - Countermeasures specific to the PFA⁸

⁸Pierre-Antoine Tissot, Lilian Bossuet, and Vincent Grosso. "BALoo: First and Efficient Countermeasure Dedicated to Persistent Fault Attacks". In: IEEE IOLTS. 2023.

1 Flash memory operation

- 2 Laser Fault Injection on unpowered devices
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Introduction	Flash memories	Laser Fault Injection on unpowered devices	X-Ray Fault Injection	Conclusion

State of the art

• Floating gate transistors erasure on powered devices thanks to X-ray exposure^{9,10,11}

Objective

• Evaluate the possibility to inject faults on unpowered devices

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⁹Stéphanie Anceau et al. "Nanofocused X-Ray Beam to Reprogram Secure Circuits". In: IACR TCHES 2017.

¹⁰Laurent Maingault et al. "Laboratory X-rays Operando Single Bit Attacks on Flash Memory Cells". In: CARDIS 2021.

¹¹S. Bouat et al. "X ray nanoprobe for fault attacks and circuit edits on 28-nm integrated circuits". In: IEEE DFT 2023.

Introduction

Conclusion

Total Ionizing Dose on MOS transistors¹²



¹² H. J. Barnaby. "Total-Ionizing-Dose Effects in Modern CMOS Technologies". In: IEEE Transactions on Nuclear Science (2006).

TID effect on MOS characteristics¹³



NMOS case

Consequences

- NMOS transistors become more easily conducting, even permanently conducting
- PMOS transistors become less easily conducting, even permanently blocking

¹³Ashok K. Sharma. Semiconductor Memories: Technology, Testing and Reliability. 2002.

TID effect on floating gate transistors¹⁴



First effect

- e^+/h^- pairs creation by radiation
- · Pairs separation by the electric field
- Electrons evacuation through the control gate
- Holes injection in the floating gate
- · Recombinaison with the stored charges
- Decrease of the stored charge

Introduction

Flash memories

Laser Fault Injection on unpowered devices

X-Ray Fault Injection

Conclusion

TID effect on floating gate transistors¹⁴



Second effect

- Charge trapping in oxides
- Not very significant given the thickness of the oxides

TID effect on floating gate transistors¹⁴



Third effect

- The stored charges obtain enough energy to overcome the potential barrier
- Decrease of the stored charge
- \Rightarrow Photoemission

TID effect on floating gate transistors¹⁴



Three different mechanims:

- Electron/hole pair generation in the oxides
- Charge trapping in the oxides
- Photoemission

Impact on threshold voltage distribution



Impact on threshold voltage distribution



Impact on threshold voltage distribution



Laser Fault Injection on unpowered devices

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Experimental setup

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ษ	HUBERT CURIE

X-ray tube	COMET MXR-165
Maximum voltage	160 kV
Maixmum current	45 mA
Anode material	Tungsten (W)
Anode angle	30°
Beam coverage	50°
Beam filtering	4 mm Beryllium (Be)



The entire target is irradiated !

Thanks to the MOPERE team Hubert Curien lab!

Target

2 levels of reading protection

- Level 0 : No restriction
- Level 1 : Flash read impossible when the *debugger* is connected



RDP	nRDP	Status	Level
OxFF	OxFF	Protected	1
OxA5	0x5A	Unprotected	0
OxXY	$\neq \overline{\text{OxXY}}$	Protected	1
OxXY	0xXY	Not specified in the documentation	?

Table 1: Flash memory protection status according to the values of RDP and nRDP
Experimental protocol

Source parameters

- 100 kV and 45 mA
- \Rightarrow Photons with 40 keV energy
- Dose rate : $1 \operatorname{Gy}_{(SiO_2)}/s$



Laser Fault Injection on unpowered devices

X-Ray Fault Injection

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Results (Flash)



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Results (Flash)



Flash memories

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Recovery phenomenon



After temporal recovery 7 days at room temperature

After thermal recovery $_{2h at 150 °C}$



 \simeq 300 000 faults





Synthesis (IEEE PAINE 2023)

Two types of faults

- Floating gate discharge by photoemission
- MOS transistor threshold voltages drift by charge trapping
 - Temporal and thermal recoveries possible

Limits

• Injection of non-localized faults that cannot be exploited

Synthesis

Two types of faults

- Floating gate discharge by photoemission
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Limits

• Injection of non-localized faults that cannot be exploited

Focusing mask conception

- Two possible materials:
 - Tungsten (W)
 - Lead (Pb)

Shield simulation



Shield	Overall attenuation
Tungsten (25 μm)	∽ 75%
Lead (25 µm)	∽ 70%

Conclusion

Tungsten mask is more efficient

Thanks to the team GPM2 of the SIMaP lab and to the CEA-Leti for the shields!

Shield simulation



Thickness	Overall attenuation
25 µm	∽ 80 %
1 mm	∽ 99.99 %

Thanks to the team GPM2 of the SIMaP lab and to the CEA-Leti for the shields!

Shield simulation



Thickness	Overall attenuation
25 µm	∽ 80 %
1 mm	

Shield efficiency

• Experimental conditions not conducive to use the mask of 25 μm

Thanks to the team GPM2 of the SIMaP lab and to the CEA-Leti for the shields!

Flash memories

Laser Fault Injection on unpowered devices

Shield simulation



Thickness	Overall attenuation
25 µm	∽ 80 %
1 mm	

Shield efficiency

 Experimental conditions not conducive to use the mask of 25 μm



Shield dimensions

Thanks to the team GPM2 of the SIMaP lab and to the CEA-Leti for the shields!

Tomograph description





Thanks to the GPM2 team of the SIMaP lab !

Pictures obtained



Infrared image overlaid on the tomograph image



Shield with a thickness of 1 mm

Irradiation campaign : Powered device

3 differents positions

- Position (1): (0.6 mm, 1.1 mm)
- Position (2): (0.6 mm, 1.2 mm)
- Position ③: (0.7 mm,1.2 mm)



Results

Approx. 40 localized faults

State of the Flash memory after 80 min exposure at the first position

Irradiation campaign : Powered device

3 differents positions

- Position (1): (0.6 mm, 1.1 mm)
- Position (2): (0.6 mm, 1.2 mm)
- Position ③: (0.7 mm,1.2 mm)



Results

Approx. 10 localized faults

State of the Flash memory after 60 min exposure at the second position

Irradiation campaign : Powered device

3 differents positions

- Position (1): (0.6 mm, 1.1 mm)
- Position (2): (0.6 mm, 1.2 mm)
- Position ③: (0.7 mm,1.2 mm)



Results

Approx. 300 localized faults

State of the Flash memory after 180 min exposure at the third position

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Irradiation campaign : Unpowered device

3 different positions

- Position (1): $(0.6 \text{ mm}, 1.2 \text{ mm}) \Rightarrow 1 \text{ h of irradiation}$
- Position (2): $(0.6 \text{ mm}, 1.1 \text{ mm}) \Rightarrow 2 \text{ h}15 \text{ min of irradiation}$



State of the Flash memory after X-ray exposure at the two positions

Results

- Approx. 70 faults localized at the position (1)
- Approx. 300 faults localized at the position (2)

Temporal evolution



Powered device

Unpowered device

Temporal evolution



Powered and unpowered device in log scale.

Conclusion

Two kind of faults

- Floating gate discharge by photoemission
- MOS transistor threshold voltages drift by charge trapping
 - Temporal and thermal recoveries (more efficient)

Fault localization (under submission)

• Possibility of focusing the faults by usint a tungsten shield 1 mm

Limits

- Shield conception limits the localization
- Few possible security attack scenarios

1 Flash memory operation

- 2 Laser Fault Injection on unpowered devices
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Conclusion

Unpowered devices

- Real threat of these attacks
- Hardware sensors are not working
- No synchronisation required

Laser

- New fault model from physical to application level
- Validation of a PFA attack scenario

X-Rays

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- Injection of permanent and non-permanent faults
- Possibility of focusing fault injection using a shield



Future works

Short term

- Secure devices (including contermeasures)
 - Hardware sensors
 - EDAC codes
- Reconfigurable circuits (FPGA, SoC-FPGA)
 - Particularly in the context of PUFs and TRNGs (ring oscillators)

Long term

- Countermeasures design
 - Systematic read physical sensors at start-up (sensitive FGmos)
 - · Analysis specific to attacks on non-powered circuits

Thank you for your attention !

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